

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended) A coating and developing apparatus comprising:
a carrier table on which at least one carrier containing a plurality of substrates is set;
a processor for applying a resist on each substrate taken out from the carrier set on the carrier table and developing the substrate after being subjected to exposing processing; ~~and~~
an interface section for transferring the resist-coated substrate between the processor and an exposing apparatus for applying the exposing processing to the resist-coated substrate, the interface section ~~including~~ having an airtight structure and located between the processor and the exposing apparatus;
at least one temperature adjuster for adjusting a temperature of the substrate to an appropriate temperature for the exposing processing before the substrate is transferred to the exposing apparatus; and
a transfer mechanism for transferring the substrate among the processor, the temperature adjuster and the exposing apparatus, the temperature adjuster and the transfer mechanism being housed in the airtight structure.

Claim 2 (Currently Amended) The coating and developing apparatus according to claim 1, ~~wherein the interface section further includes~~ further comprising:
a peripheral exposing apparatus for exposing a periphery of the substrate outside a circuit-forming area thereon to ultraviolet radiation, the peripheral exposing apparatus being housed in the airtight structure, wherein the transfer mechanism ~~transfer~~ transfers the substrate among the processor, the temperature adjuster and the peripheral exposing apparatus.

Claim 3 (Original) The coating and developing apparatus according to claim 2, wherein the interface section includes a plurality of temperature adjusters stacked under the peripheral exposing apparatus.

Claim 4 (Currently Amended) The coating and developing apparatus according to claim 1, wherein the temperature adjuster adjusts a temperature of the substrate ~~for~~ of which the periphery of the substrate outside a circuit-forming area thereon has been exposed, to the appropriate temperature for the exposing processing.

Claim 5 (Currently Amended) The coating and developing apparatus according to claim 1, wherein the interface section further includes a clean-air filter unit, air passed ~~through~~ through the clean-air filter unit being flown down into the interface section.

Claim 6 (Currently Amended) The coating and developing apparatus according to claim 5, wherein the interface section further includes an electrical unit housing electrical facility, the air passed ~~through~~ through the clean-air filter unit being also flown down into a space for the electrical unit in the interface section.

Claim 7 (Currently Amended) A coating and developing apparatus comprising:
a carrier table on which at least one carrier containing a plurality of substrates is set;
a processor for applying a resist on each substrate taken out from the carrier set on the carrier table and developing the substrate after being subjected to exposing processing; ~~and~~
an interface section for transferring the resist-coated substrate between the processor

and an exposing apparatus for applying the exposing processing to the resist-coated substrate, the interface section including having an airtight structure and located between the processor and the exposing apparatus;

a shelf section having a plurality of processing units for containing or processing the substrate;

a first transfer mechanism for transferring the substrate between the processor and the exposing apparatus; and

a second transfer mechanism for receiving the substrate transferred from the processor by the first transfer mechanism and transferring the received substrate to any of the units of the shelf section, the shelf section and the first and second transfer mechanisms being housed in the airtight structure.

Claim 8 (Original) The coating and developing apparatus according to claim 7, wherein the shelf section of the interface section includes at least one temperature adjuster for adjusting a temperature of the substrate to an appropriate temperature for the exposing processing before the substrate is transferred to the exposing apparatus, the substrate being transferred to the temperature adjuster by the first and/or the second transfer mechanisms.

Claim 9 (Currently Amended) The coating and developing apparatus according to claim 7, ~~wherein the interface section further includes~~ further comprising:

a peripheral exposing apparatus, as one of the units, for exposing periphery of the substrate outside a circuit-forming area thereon to ultraviolet radiation, the peripheral exposing apparatus being housed in the airtight structure, the substrate that has been transferred from the processor by the first transfer mechanism being transferred to the

peripheral exposing apparatus by the second transfer mechanism.

Claim 10 (Original) The coating and developing apparatus according to claim 7, wherein the interface section further includes a loading unit, as one of the units, for loading the substrate between the first and the second transfer mechanisms, the substrate being transferred among the processor, the exposing apparatus and the loading unit by the first transfer mechanism and being transferred between the loading unit and any of the units of the shelf section by the second transfer mechanism.

Claim 11 (Original) The coating and developing apparatus according to claim 8, wherein the temperature adjuster adjusts the temperature of the substrate, of which the periphery outside the circuit-forming area thereon has been exposed, to the appropriate temperature for the exposing processing.

Claim 12 (Original) The coating and developing apparatus according to claim 7, wherein the processing units are stacked in the shelf section.

Claim 13 (Currently Amended) The coating and developing apparatus according to claim 7, wherein the first and the second transfer mechanisms are aligned on ~~[[a]]~~ an almost straight line, as the first and the second transfer mechanisms face each other with the shelf section interposed therebetween, in a direction almost parallel to another direction in which the carrier is set on the carrier table.

Claim 14 (Original) The coating and developing apparatus according to claim 7,

wherein the first transfer mechanism has an arm for transferring the substrate, that is movable upward, downward, forward and backward and rotatable about a vertical axis, and movable in a direction of a horizontal axis.

Claim 15 (Original) The coating and developing apparatus according to claim 7, wherein the second transfer mechanism has an arm for transferring the substrate, that is movable upward, downward, forward and backward and rotatable about a vertical axis.

Claim 16 (Currently Amended) The coating and developing apparatus according to claim 7, wherein the interface section further includes a clean-air filter unit, air passed ~~through~~ through the clean-air filter unit being flown down into the interface section.

Claim 17 (Currently Amended) The coating and developing apparatus according to claim 16, wherein the interface section further includes an electrical unit housing electrical facility, the air passed ~~through~~ through the clean-air filter unit being also flown down into a space for the electrical unit in the interface section.

Claims 18-22 (Cancelled)

Claim 23 (New) A coating and developing apparatus comprising:
a carrier table on which at least one carrier containing a plurality of substrates is set;
a processor for applying a resist on each substrate taken out from the carrier set on the carrier table and developing the substrate after being subjected to exposing

processing;

an interface section for transferring the resist-coated substrate between the processor and an exposing apparatus for applying the exposing processing to the resist-coated substrate, the interface section having an airtight structure and located between the processor and the exposing apparatus;

at least one temperature adjuster for adjusting a temperature of the substrate to an appropriate temperature for the exposing processing before the substrate is transferred to the exposing apparatus;

a transfer mechanism for transferring the substrate among the processor, the temperature adjuster and the exposing apparatus; and

a peripheral exposing apparatus for exposing periphery of the substrate outside a circuit-forming area thereon to ultraviolet radiation, the transfer mechanism transferring the substrate among the processor, the temperature adjuster, and the peripheral exposing apparatus, and wherein

the transfer mechanism is housed in the airtight structure.